

ROTARY WAFER PROCESSING APPARATUS

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- european:

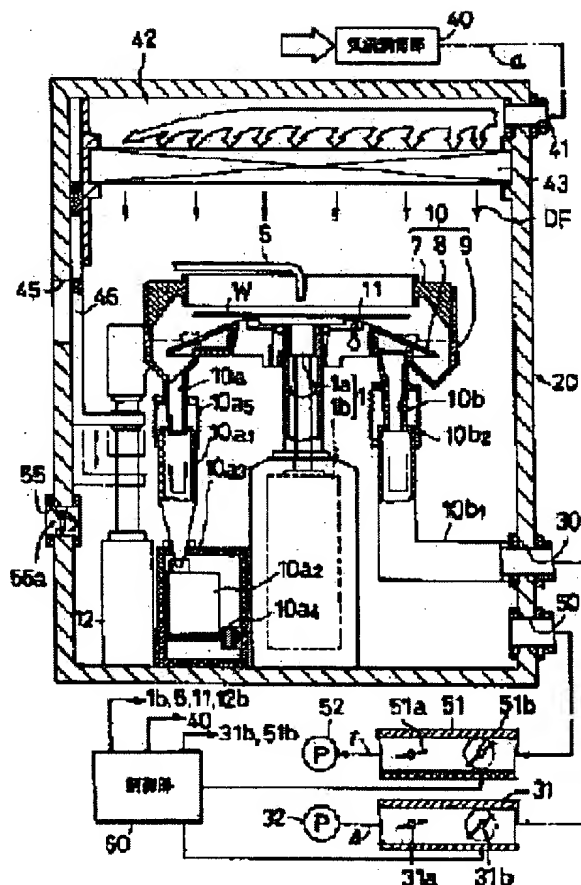
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Abstract of JP9148231

PROBLEM TO BE SOLVED: To remove mist and odors leaking from a scatter preventive cup to prevent the contamination of wafers both inside and outside a wafer processing apparatus, while taking measures for safety and hygiene. **SOLUTION:** A rotary wafer processing apparatus comprises a rotational drive 1 for rotating a wafer W; a nozzle 5 for emitting liquid photoresist; a cup 10 that surrounds the wafer W to prevent photoresist from scattering; and a housing 20 that encloses all the foregoing members, allows a downflow DF within it and includes an exhaust 30 for discharging the cup 10. The housing 20 is provided with another exhaust 50 for discharging the downflow DF, and the exhaust 50 is communicating with an automatic damper 51b for exhaust control.



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